

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	695	(MEMS or "micro electromechanical system") same pattern\$3 same actuator	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 10:20
L2	452	1 and etch\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 09:18
L3	343	(MEMS or "micro electromechanical system") same mask\$3 same actuator	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 09:29
L4	780	(MEMS or "micro electromechanical system") same etch\$4 same actuator	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 09:48
L5	2	"5316640".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 09:47
L6	2	"5853959".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 09:47
L7	403	(MEMS or "micro electromechanical system") and etch\$4 and actuator and slider	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 09:52
L8	229	7 and semiconductor	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 09:57

L9	1642	(MEMS or "micro electromechanical system") same pattern\$3 same etch\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 10:07
L10	826	9 and actuator	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 09:57
L11	626	10 and semiconductor	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 10:22
L12	383	(MEMS or "micro electromechanical system") with pattern\$3 with etch\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 10:19
L13	2337	mask same round\$3 same etch\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 10:22
L18	253	(resist or photoresist) same round\$3 same etch\$4 same plasma	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 10:23